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Nanotechnology and microengineering are among the top priority research areas for the US and Europe. This text provides coverage of all aspects of the attempt to build functional devices at a molecular size. The acquisition and interpretation of images is a central capability in almost all scientific and technological domains. In particular, the acquisition of electromagnetic radiation, in the form of visible light, UV, infrared, X-ray, etc. is of enormous practical importance. The ultimate sensitivity in electronic imaging is the detection of individual photons. With this book, the first comprehensive review of all aspects of single-photon electronic imaging has been created. Topics include theoretical basics, semiconductor fabrication, single-photon detection principles, imager design and applications of different spectral domains. Today, the solid-state fabrication capabilities for several types of image sensors has advanced to a point, where uncoooled single-photon electronic imaging will soon become a consumer product. This book is giving a specialist´s view from different domains to the forthcoming “single-photon imaging” revolution. The various aspects of single-photon imaging are treated by internationally renowned, leading scientists and technologists who have all pioneered their respective fields. Beginning in the mid 1980's, VLSI technology had begun to advance in two directions. Pushing the limit of integration, ULSI (Ultra Large Scale Integration) represents the frontier of the semiconductor processing technology in the campaign to conquer the submicron realm. The application of ULSI, however, is at present largely confined in the area of memory designs, and as such, its impact on traditional, microprocessor-based system design is modest. If advancement in this direction is merely a natural extrapolation from the previous integration generations, then the rise of ASIC (Application-Specific Integrated Circuit) is an unequivocal signal that a directional change in the discipline of system design is in effect. In contrast to ULSI, ASIC employs only well proven technology, and hence is usually at least one generation behind the most advanced processing technology. In spite of this apparent disadvantage, ASIC has become the mainstream of VLSI design and the technology base of numerous entrepreneurial opportunities ranging from PC clones to supercomputers. Unlike ULSI whose complexity can be hidden inside a memory chip or a standard component and thus can be accommodated by traditional system design methods, ASIC requires system designers to master a much larger body of knowledge spanning from processing technology and circuit techniques to architecture principles and algorithm characteristics. Integrating knowledge in these various areas has become the precondition for integrating devices and functions into an ASIC chip in a market-oriented environment. But knowledge is of two kinds. This book is a comprehensive guide to new DFT methods that will show the readers how to design a testable and quality product,

drive down test cost, improve product quality and yield, and speed up time-to-market and time-to-volume. Most up-to-date coverage of design for testability. Coverage of industry practices commonly found in commercial DFT tools but not discussed in other books. Numerous, practical examples in each chapter illustrating basic VLSI test principles and DFT architectures. A selection of studies by professionals in the semiconductor industry illustrating the use of statistical methods to improve manufacturing processes. This monograph is motivated by the challenges faced in designing reliable VLSI systems in modern VLSI processes. The reliable operation of integrated circuits (ICs) has become increasingly dif?cult to achieve in the deep submicron (DSM) era. With continuouslydecreasing device feature sizes, combinedwith lower supply voltages and higher operating frequencies, the noise immunity of VLSI circuits is decreasing alarmingly. Thus, VLSI circuits are becoming more vulnerable to noise effects such as crosstalk, power supply variations, and radiation-inducedsoft errors. Among these noise sources, soft errors(or error caused by radiation particle strikes) have become an increasingly troublesome issue for memory arrays as well as c-binational logic circuits. Also, in the DSM era, process variations are increasing at a signi?cant rate, making it more dif?cult to design reliable VLSI circuits. Hence, it is important to ef?ciently design robust VLSI circuits that are resilient to radiation particle strikes and process variations. The work presented in this research mo- graph presents several analysis and design techniques with the goal of realizing VLSI circuits, which are radiation and process variation tolerant. Advances in solid state materials provide an important driving force in the development of modern society, playing a vital role in almost all aspects ofscience and technology. This book presents the contributions to an international workshop on solid state materials, organized to providehands-on experience to scientists from a wide range of relevant disciplines.The topics discussed fall into the categories solid state ionic materials, laser materials, semiconductors and superconducting materials. A Fully Integrated Presentation of New Hardware and Software Product Introductions Using Program Management Methodologies for System on Chip Platforms If you're an executive, manager, or engineer in the semiconductor, software, or systems industries, this book provides conceptual views ranging from the design of integrated circuits or systems on a chip, through fabrication, to integration of chips onto boards, and through development of enablement and runtime software for system and platform deliveries. Special features included this book are: - Program management methodologies - General management fundamentals - An overview of leadership principles - Basic discrete device technology - Internal structure and operation of some common logic gates - Basic integrated circuit design concepts, building blocks, and flow - Chip packaging technologies - Details of the fabrication process for integrated circuits - Printed circuit board design, manufacture, and test - Software design, development, and test - Integrated circuit test, silicon validation, and device qualification - Program management applications bringing it all together The book explores interactions and dependencies of technologies that impact systems and platforms. This is a valuable resource to learn these technologies or to use as a reference. A systematic description of microelectronic device design. Topics range from the basics to low-power and ultralow-voltage designs, subthreshold current reduction, memory subsystem designs for modern DRAMs, and various on-chip supply-voltage conversion techniques. It also covers process and device issues as well as design issues relating to systems, circuits, devices and processes, such as signal-to-noise and redundancy. A practical guide to semiconductor manufacturing from processcontrol to yield modeling and experimental design Fundamentals of Semiconductor Manufacturing and Process Controlcovers all issues involved in manufacturing microelectronic devicesand circuits, including fabrication sequences, process control,experimental design, process modeling, yield modeling, and CIM/CAMsystems. Readers are introduced to both the theory and practice ofall basic manufacturing concepts. Following an overview of manufacturing and technology, the textexplores process monitoring methods, including those that focus onproduct wafers and those that focus on the equipment used toproduce wafers. Next, the text sets forth some fundamentals ofstatistics and yield modeling, which set the foundation for adetailed discussion of how statistical process control is used toanalyze quality and improve yields. The discussion of statistical experimental design offers readers apowerful approach for systematically varying controllable processconditions and determining their impact on output parameters thatmeasure quality. The authors introduce process modeling concepts,including several advanced process control topics such asrun-by-run, supervisory control, and process and equipmentdiagnosis. Critical coverage includes the following: * Combines process control and semiconductor manufacturing * Unique treatment of system and software technology and managementof overall manufacturing systems * Chapters include case studies, sample problems, and suggestedexercises * Instructor support includes electronic copies of the figures andan instructor's manual Graduate-level students and industrial practitioners will benefitfrom the detailed exami?nation of how electronic materials andsupplies are converted into finished integrated circuits andelectronic products in a high-volume manufacturingenvironment. An Instructor's Manual presenting detailed solutions to all theproblems in the book is available from the Wiley editorialdepartment. An Instructor Support FTP site is also available. This book facilitates the VLSI-interested individuals with not only in-depth knowledge, but also the broad aspects of it by explaining its applications in different fields, including image processing and biomedical. The deep understanding of basic concepts gives you the power to develop a new application aspect, which is very well taken care of in this book by using simple language in explaining the concepts. In the VLSI world, the importance of hardware description languages cannot be ignored, as the designing of such dense and complex circuits is not possible without them. Both Verilog and VHDL languages are used here for designing. The current needs of high-performance integrated circuits (ICs) including low power devices and new emerging materials, which can play a very important role in achieving new functionalities, are the most interesting part of the book. The testing of VLSI circuits becomes more crucial than the designing of the circuits in this nanometer technology era. The role of fault simulation algorithms is very well explained, and its implementation using Verilog is the key aspect of this book. This book is well organized into 20 chapters. Chapter 1 emphasizes on uses of FPGA on various image processing and biomedical applications. Then, the descriptions enlighten the basic understanding of digital design from the perspective of HDL in Chapters 2–5. The performance enhancement with alternate material or geometry for silicon-based FET designs is focused in Chapters 6 and 7. Chapters 8 and 9 describe the study of bimolecular interactions with biosensing FETs. Chapters 10–13 deal with advanced FET structures available in various shapes, materials such as nanowire, HFET, and their comparison in terms of device performance metrics calculation. Chapters 14–18 describe different application-specific VLSI design techniques and challenges for analog and digital circuit designs. Chapter 19 explains the VLSI testability issues with the description of simulation and its categorization into logic and fault simulation for test pattern generation using Verilog HDL. Chapter 20 deals with a secured VLSI design with hardware obfuscation by hiding the IC’s structure and function, which makes it much more difficult to reverse engineer. This collection of essays focuses on the changing role of firms and states in shaping international competition. The way in which industry responds to this situation by forming strategic alliances both within industrial sectors and across national borders is examined. In this book, a variety of topics related to Very-Large-Scale Integration (VLSI) is extensively discussed. The topics encompass the physics of VLSI transistors, the process of integrated chip design and fabrication and the applications of VLSI devices. It is intended to provide information on the latest advancement of VLSI technology to researchers, physicists as well as engineers working in the field of semiconductor manufacturing and VLSI design. Semiconductor Silicon Crystal Technology provides information pertinent to silicon, which is the dominant material in the semiconductor industry. This book discusses the technology of integrated circuits (ICs) in electronic materials manufacturer. Comprised of eight chapters, this book provides an overview of the basic science, silicon materials, IC device fabrication processes, and their interaction for enhancing both the processes and materials. This text then proceeds with a discussion of the atomic structure and bonding mechanisms in order to understand the nature and formation of crystal structures, which are the fundamentals of material science. Other chapters consider the technological crystallography and classify natural crystal morphologies based on observation. The final chapter deals with the interrelationships among silicon material characteristics, circuit design, and IC fabrication in order to ensure the fabrication of very-large-scale-integration/ultra-large-scale-integration circuits. This book is a valuable resource for graduate students, physicists, engineers, materials scientists, and professionals involved in semiconductor industry. This book provides readers with

an up-to-date account of the use of machine learning frameworks, methodologies, algorithms and techniques in the context of computer-aided design (CAD) for very-large-scale integrated circuits (VLSI). Coverage includes the various machine learning methods used in lithography, physical design, yield prediction, post-silicon performance analysis, reliability and failure analysis, power and thermal analysis, analog design, logic synthesis, verification, and neuromorphic design. Provides up-to-date information on machine learning in VLSI CAD for device modeling, layout verifications, yield prediction, post-silicon validation, and reliability; Discusses the use of machine learning techniques in the context of analog and digital synthesis; Demonstrates how to formulate VLSI CAD objectives as machine learning problems and provides a comprehensive treatment of their efficient solutions; Discusses the tradeoff between the cost of collecting data and prediction accuracy and provides a methodology for using prior data to reduce cost of data collection in the design, testing and validation of both analog and digital VLSI designs. From the Foreword As the semiconductor industry embraces the rising swell of cognitive systems and edge intelligence, this book could serve as a harbinger and example of the osmosis that will exist between our cognitive structures and methods, on the one hand, and the hardware architectures and technologies that will support them, on the other....As we transition from the computing era to the cognitive one, it behooves us to remember the success story of VLSI CAD and to earnestly seek the help of the invisible hand so that our future cognitive systems are used to design more powerful cognitive systems. This book is very much aligned with this on-going transition from computing to cognition, and it is with deep pleasure that I recommend it to all those who are actively engaged in this exciting transformation. Dr. Ruchir Puri, IBM Fellow, IBM Watson CTO & Chief Architect, IBM T. J. Watson Research Center The explosive growth and development of the integrated circuit market over the last few years have been mostly limited to the digital VLSI domain. The difficulty of automating the design process in the analog domain, the fact that a general analog design methodology remained undefined, and the poor performance of earlier tools have left the analog Retaining the comprehensive and in-depth approach that cemented the bestselling first edition's place as a standard reference in the field, the Handbook of Semiconductor Manufacturing Technology, Second Edition features new and updated material that keeps it at the vanguard of today's most dynamic and rapidly growing field. Iconic experts Robert Doering and Yoshio Nishi have again assembled a team of the world's leading specialists in every area of semiconductor manufacturing to provide the most reliable, authoritative, and industry-leading information available. Stay Current with the Latest Technologies In addition to updates to nearly every existing chapter, this edition features five entirely new contributions on... Silicon-on-insulator (SOI) materials and devices Supercritical CO2 in semiconductor cleaning Low-κ dielectrics Atomic-layer deposition Damascene copper electroplating Effects of terrestrial radiation on integrated circuits (ICs) Reflecting rapid progress in many areas, several chapters were heavily revised and updated, and in some cases, rewritten to reflect rapid advances in such areas as interconnect technologies, gate dielectrics, photomask fabrication, IC packaging, and 300 mm wafer fabrication. While no book can be up-to-the-minute with the advances in the semiconductor field, the Handbook of Semiconductor Manufacturing Technology keeps the most important data, methods, tools, and techniques close at hand. This book describes methodologies in the design of VLSI devices, circuits and their applications at nanoscale levels. The book begins with the discussion on the dominant role of power dissipation in highly scaled devices.The 15 Chapters of the book are classified under four sections that cover design, modeling, and simulation of electronic, magnetic and compound semiconductors for their applications in VLSI devices, circuits, and systems. This comprehensive volume eloquently presents the design methodologies for ultra–low power VLSI design, potential post–CMOS devices, and their applications from the architectural and system perspectives. The book shall serve as an invaluable reference book for the graduate students, Ph.D./ M.S./ M.Tech. Scholars, researchers, and practicing engineers working in the frontier areas of nanoscale VLSI design. VLSI-Design for Non-Volatile Memories is intended for electrical engineers and graduate students who want to enter into the integrated circuit design world. Non-volatile memories are treated as an example to explain general design concepts. Practical illustrative examples of non-volatile memories, including flash types, are showcased to give insightful examples of the discussed design approaches. A collection of photos is included to make the reader familiar with silicon aspects. Throughout all parts of this book, the authors have taken a practical and applications-driven point of view, providing a comprehensive and easily understood approach to all the concepts discussed. Giovanni Campardo and Rino Micheloni have a solid track record of leading design activities at the STMicroelectronics Flash Division. David Novosel is President and founder of Intelligent Micro Design, Inc., Pittsburg, PA. This issue of ECS Transactions contains the papers presented in the symposium on Silicon Nitride, Silicon Dioxide Thin Insulating Films, and Emerging Dielectics held May 6-11, 2007 in Chicago. Papers were presented on deposition, characterization and applications of the dielectrics including high- and low-k dielectrics, as well as interface states, device characterization, reliabiliy and modeling. The world of microelectronics is filled with cusses measurement systems, manufacturing many success stories. From the use of semi control techniques, test, diagnostics, and fail ure analysis. It discusses methods for modeling conductors for powerful desktop computers to their use in maintaining optimum engine per and reducing defects, and for preventing de formance in modem automobiles, they have fects in the first place. The approach described, clearly improved our daily lives. The broad while geared to the microelectronics world, has useability of the technology is enabled, how applicability to any manufacturing process of similar complexity. The authors comprise some ever, only by the progress made in reducing their cost and improving their reliability. De of the best scientific minds in the world, and fect reduction receives a significant focus in our are practitioners of the art. The information modem manufacturing world, and high-quality captured here is world class. I know you will diagnostics is the key step in that process. find the material to be an excellent reference in of product failures enables step func Analysis your application. tion improvements in yield and reliability. which works to reduce cost and open up new Dr. Paul R. Low applications and technologies. IBM Vice President and This book describes the process ofdefect re of Technology Products General Manager duction in the microelectronics world. Semiconductor sensors patterned at the micron scale combined with custom-designed integrated circuits have revolutionized semiconductor radiation detector systems. Designs covering many square meters with millions of signal channels are now commonplace in high-energy physics and the technology is finding its way into many other fields, ranging from astrophysics to experiments at synchrotron light sources and medical imaging. This book is the first to present a comprehensive discussion of the many facets of highly integrated semiconductor detector systems, covering sensors, signal processing, transistors and circuits, low-noise electronics, and radiation effects. The diversity of design approaches is illustrated in a chapter describing systems in high-energy physics, astronomy, and astrophysics. Finally a chapter "Why things don't work" discusses common pitfalls. Profusely illustrated, this book provides a unique reference in a key area of modern science. Silicon, as a single-crystal semiconductor, has sparked a revolution in the field of electronics and touched nearly every field of science and technology. Though available abundantly as silica and in various other forms in nature, silicon is difficult to separate from its chemical compounds because of its reactivity. As a solid, silicon is chemically inert and stable, but growing it as a single crystal creates many technological challenges. Crystal Growth and Evaluation of Silicon for VLSI and ULSI is one of the first books to cover the systematic growth of silicon single crystals and the complete evaluation of silicon, from sand to useful wafers for device fabrication. Written for engineers and researchers working in semiconductor fabrication industries, this practical text: Describes different techniques used to grow silicon single crystals Explains how grown single-crystal ingots become a complete silicon wafer for integrated-circuit fabrication Reviews different methods to evaluate silicon wafers to determine suitability for device applications Analyzes silicon wafers in terms of resistivity and impurity concentration mapping Examines the effect of intentional and unintentional impurities Explores the defects found in regular silicon-crystal lattice Discusses silicon wafer preparation for VLSI and ULSI processing Crystal Growth and Evaluation of Silicon for VLSI and ULSI is an essential reference for different approaches to the selection of the basic silicon-containing compound, separation of silicon as metallurgical-grade pure silicon, subsequent purification, single-crystal growth, and defects and evaluation of the deviations within the grown crystals. This book examines and projects the critical technologies involved in the fabrication of very large scale integration (VLSI) semiconductor devices, including their likely developments, why and when their introduction or demise will take place, what

problems and choices are facing the industry, and where the opportunities and pitfalls may exist. Written from an industry perspective, this book emphasizes the most rapid technological advances in the semiconductor industry, and addresses the strategic issues impacting both the user and the supplier of chemicals, materials and equipment. The book assists the reader in evaluating the spectrum of products and systems available for use at every crucial stage in the processing of an advanced integrated circuit (IC) device. To the suppliers, the book offers insight for future user needs and will assist them in long-range planning, and new product development and improvement. Topics discussed in detail include contamination control; thin film deposition and et In this book leading profesionals in the semiconductor microelectronics field discuss the future evolution of their profession. The following are some of the questions discussed: Does CMOS technology have a real problem? Do transistors have to be smaller or just better and made of better materials? What is to come after semiconductors? Superconductors or molecular conductors? Is bottom-up self-assembling the answer to the limitation of top-down lithography? Is it time for Optics to become a force in computer evolution? Quantum Computing, Spintronics? Where is the printable plastic electronics proposed 10 years ago? Are carbon nanotube transistors the CMOS of the future? This volume analyzes and summarizes recent developments in several key interfacial electrochemical systems in the areas of fuel cell electrocatatalysis, electrosynthesis and electrodeposition. The six Chapters are written by internationally recognized experts in these areas and address both fundamental and practical aspects of several existing or emerging key electrochemical technologies. The Chapter by R. Adzic, N. Marinkovic and M. Vukmirovic provides a lucid and authoritative treatment of the electrochemistry and electrocatalysis of Ruthenium, a key element for the devel- ment of efficient electrodes for polymer electrolyte (PEM) fuel cells. Starting from fundamental surface science studies and interfacial considerations, this up-to-date review by some of the pioneers in this field, provides a deep insight in the complex catalytic-electrocatalytic phenomena occurring at the interfaces of PEM fuel cell electrodes and a comprehensive treatment of recent developments in this extremely important field. Several recent breakthroughs in the design of solid oxide fuel cell (SOFC) anodes and cathodes are described in the Chapter of H. Uchida and M. Watanabe. The authors, who have pioneered several of these developments, provide a lucid presentation d- cribing how careful fundamental investigations of interfacial electrocatalytic anode and cathode phenomena lead to novel electrode compositions and microstructures and to significant practical advances of SOFC anode and cathode stability and enhanced electrocatalysis. P. Antognetti University of Genova, Italy Director of the NATO ASI The key importance of VLSI circuits is shown by the national efforts in this field taking place in several countries at differ ent levels (government agencies, private industries, defense de partments). As a result of the evolution of IC technology over the past two decades, component complexi ty has increased from one single to over 400,000 transistor functions per chip. Low cost of such single chip systems is only possible by reducing design cost per function and avoiding cost penalties for design errors. Therefore, computer simulation tools, at all levels of the design process, have become an absolute necessity and a cornerstone in the VLSI era, particularly as experimental investigations are very time-consuming, often too expensive and sometimes not at all feasible. As minimum device dimensions shrink, the need to understand the fabrication process in a quanti tati ve way becomes critical. Fine patterns, thin oxide layers, polycristalline silicon interco~ nections, shallow junctions and threshold implants, each become more sensitive to process variations. Each of these technologies changes toward finer structures requires increased understanding of the process physics. In addition, the tighter requirements for process control make it imperative that sensitivities be unde~ stood and that optimation be used to minimize the effect of sta tistical fluctuations. The Complete, Modern Tutorial on Practical VLSI Chip Design, Validation, and Analysis As microelectronics engineers design complex chips using existing circuit libraries, they must ensure correct logical, physical, and electrical properties, and prepare for reliable foundry fabrication. VLSI Design Methodology Development focuses on the design and analysis steps needed to perform these tasks and successfully complete a modern chip design. Microprocessor design authority Tom Dillinger carefully introduces core concepts, and then guides engineers through modeling, functional design validation, design implementation, electrical analysis, and release to manufacturing. Writing from the engineer’s perspective, he covers underlying EDA tool algorithms, flows, criteria for assessing project status, and key tradeoffs and interdependencies. This fresh and accessible tutorial will be valuable to all VLSI system designers, senior undergraduate or graduate students of microelectronics design, and companies offering internal courses for engineers at all levels. Reflect complexity, cost, resources, and schedules in planning a chip design project Perform hierarchical design decomposition, floorplanning, and physical integration, addressing DFT, DFM, and DFY requirements Model functionality and behavior, validate designs, and verify formal equivalency Apply EDA tools for logic synthesis, placement, and routing Analyze timing, noise, power, and electrical issues Prepare for manufacturing release and bring-up, from mastering ECOs to qualification This guide is for all VLSI system designers, senior undergraduate or graduate students of microelectronics design, and companies offering internal courses for engineers at all levels. It is applicable to engineering teams undertaking new projects and migrating existing designs to new technologies. A Comprehensive, Thorough Introduction to High-Speed Networking Technologies and Protocols Network Infrastructure and Architecture: Designing High-Availability Networks takes a unique approach to the subject by covering the ideas underlying networks, the architecture of the network elements, and the implementation of these elements in optical and VLSI technologies. Additionally, it focuses on areas not widely covered in existing books: physical transport and switching, the process and technique of building networking hardware, and new technologies being deployed in the marketplace, such as Metro Wave Division Multiplexing (MWDM), Resilient Packet Rings (RPR), Optical Ethernet, and more. Divided into five succinct parts, the book covers: Optical transmission Networking protocols VLSI chips Data switching Networking elements and design Complete with case studies, examples, and exercises throughout, the book is complemented with chapter goals, summaries, and lists of key points to aid readers in grasping the material presented. Network Infrastructure and Architecture offers professionals, advanced undergraduates, and graduate students a fresh view on high-speed networking from the physical layer perspective. Examines all important aspects of integrated circuit design, fabrication, assembly and test processes as they relate to quality and reliability. This second edition discusses in detail: the latest circuit design technology trends; the sources of error in wafer fabrication and assembly; avenues of contamination; new IC packaging methods; new in-line process monitors and test structures; and more.;This work should be useful to electrical and electronics, quality and reliability, and industrial engineers; computer scientists; integrated circuit manufacturers; and upper-level undergraduate, graduate and continuing-education students in these disciplines. This book explains in layman’s terms how CMOS transistors work. The author explains step-by-step how CMOS transistors are built, along with an explanation of the purpose of each process step. He describes for readers the key inventions and developments in science and engineering that overcame huge obstacles, enabling engineers to shrink transistor area by over 1 million fold and build billions of transistor switches that switch over a billion times a second, all on a piece of silicon smaller than a thumbnail. Asynchronous System-on-Chip Interconnect describes the use of an entirely asynchronous system-bus for the modular construction of integrated circuits. Industry is just awakening to the benefits of asynchronous design in avoiding the problems of clock-skew and multiple clock-domains, an din parallel with this is coming to grips with Intellectual Property (IP) based design flows which emphasise the need for a flexible interconnect strategy. In this book, John Bainbridge investigates the design of an asynchronous on-chip interconnect, looking at all the stages of the design from the choice of wiring layout, through asynchronous signalling protocols to the higher level problems involved in supporting split transactions. The MARBLE bus (the first asynchronous SoC bus) used in a commercial demonstrator chip containing a mixture of asynchronous and synchronous macrocells is used as a concrete example throughout the book. With the world marching inexorably towards the fourth industrial revolution (IR 4.0), one is now embracing lives with artificial intelligence (AI), the Internet of Things (IoTs), virtual reality (VR) and 5G technology. Wherever we are, whatever we are doing, there are electronic devices that we rely indispensably on. While some of these technologies, such as those fueled with smart, autonomous systems, are seemingly precocious; others have existed for quite a while. These devices range from simple home appliances, entertainment media to complex aeronautical instruments. Clearly, the daily lives of mankind today are interwoven seamlessly with electronics. Surprising as it may

seem, the cornerstone that empowers these electronic devices is nothing more than a mere diminutive semiconductor cube block. More colloquially referred to as the Very-Large-Scale-Integration (VLSI) chip or an integrated circuit (IC) chip or simply a microchip, this semiconductor cube block, approximately the size of a grain of rice, is composed of millions to billions of transistors. The transistors are interconnected in such a way that allows electrical circuitries for certain applications to be realized. Some of these chips serve specific permanent applications and are known as Application Specific Integrated Circuits (ASICS); while, others are computing processors which could be programmed for diverse applications. The computer processor, together with its supporting hardware and user interfaces, is known as an embedded system.In this book, a variety of topics related to microchips are extensively illustrated. The topics encompass the physics of the microchip device, as well as its design methods and applications.